L Number	Hits	Search Text	DB	Time stamp
87	45	(((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/07/22 15:20
88	0	<pre>((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))</pre>	DERWENT	2003/07/22 15:32
89		not us.pc. (430/314,323-324.ccls. not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))) not us.pc.	DERWENT	2003/07/22 15:32
90	26	<pre>((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))</pre>	USPAT; US-PGPUB; EPO; JPO; ~ IBM_TDB	2003/07/22 15:34
91	3048	430/314,323-324.ccls. not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/07/22 15:44
92	36	((mems or moems or microelectromechanical or micro adj electromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/07/22 15:39
93	915	(((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not 430/314,323-324.ccls.) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/07/22 15:40
94	18	resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/07/22 15:40
95	36	430/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/07/22
96	11	<pre>(resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/07/22

97	1	((resist or photoresist) and	USPAT;	2003/07/22
		((microplatform or suspend\$3) same	US-PGPUB;	15:41
,		(slop\$3 or inclin\$3 or taper\$3))) and	EPO; JPO;	
		((grey or gray) with mask)	IBM_TDB	0002/07/22
98	2	(resist or photoresist) and ((microbeam)	USPAT;	2003/07/22
		same (slop\$3 or inclin\$3 or taper\$3))	US-PGPUB;	16:18
			EPO; JPO;	
	_		IBM_TDB	0000 (07 (00
99	17	(((slop\$3 or inclin\$3 or taper\$3) with	USPAT;	2003/07/22
		(etch\$3)) and 430/320.ccls.) not	US-PGPUB;	15:43
		((((resist or photoresist) and (slop\$3 or	EPO; JPO;	
		inclin\$3 or taper\$3)) with (etch\$3)) and	IBM_TDB	
	ļ	((grey or gray) same (mask or reticle)))		
		not (((((resist or photoresist) and		
		(slop\$3 or inclin\$3 or taper\$3)) same		
		(etch\$3)) and ((grey or gray) same		
	ì	(photomask or mask or reticle))) not		
		((((resist or photoresist) and (slop\$3 or		
		inclin\$3 or taper\$3)) with (etch\$3)) and		
	1	((grey or gray) same (photomask or mask		
		or reticle)))) not (430/314,323-324.ccls.		1
		not ((((resist or photoresist) and		
		(slop\$3 or inclin\$3 or taper\$3)) with		
		(etch\$3)) and ((grey or gray) same		
		(photomask or mask or reticle))) not		
		(((((resist or photoresist) and (slop\$3		
		or inclin\$3 or taper\$3)) same (etch\$3))		
		and ((grey or gray) same (photomask or		
		mask or reticle))) not ((((resist or		I
		photoresist) and (slop\$3 or inclin\$3 or		
		taper\$3)) with (etch\$3)) and ((grey or		ŀ
		gray) same (photomask or mask or		
		reticle))))) not (((mems or moems or		
		microelectromechanical or micro adj		
		electromechanical).ti.ab.) and (microbeam		
		or microplatform or microsupport or		
		(suspend\$3 with microstructure))) not		
		((((photolithograph\$6 or lithograph\$6 or		
		photoresist or resist) and etch\$3 and		
		(204/192.14-192.15,192.17,192.23,192.25		
		or 205/122-123,125).ccls.) not		
		430/314,323-324.ccls.) not ((((resist or		
		photoresist) and (slop\$3 or inclin\$3 or		
		taper\$3)) with (etch\$3)) and ((grey or		
•		gray) same (mask or reticle)))) not		
	1	(resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or		
	1	resist) same etch\$3)) not		
		resist) same etch\$3)) not (430/314,323-324.ccls. and (planarization		
		adj layer) not ((((resist or photoresist)		1
	1	adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with		
		and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same		
		(photomask or mask or reticle))) not		
		(((((resist or photoresist) and (slop\$3		
		or inclin\$3 or taper\$3)) same (etch\$3))	İ	
		and ((grey or gray) same (photomask or		
		mask or reticle))) not ((((resist or		
		photoresist) and (slop\$3 or inclin\$3 or		
		taper\$3)) with (etch\$3)) and ((grey or	-	
		gray) same (photomask or mask or		
		reticle))))) not ((resist or photoresist)		
		and (air adj bridge same (slop\$3 or		
		inclin\$3 or taper\$3))) not ((resist or		
		photoresist) and ((microbeam) same		
		(slop\$3 or inclin\$3 or taper\$3)))		
_	830	(((resist or photoresist) and (slop\$3 or	USPAT;	2003/01/24
-	030	inclin\$3 or taper\$3)) and (etch\$3)) and	US-PGPUB;	16:24
		(grey or gray)	EPO; JPO;	13.21
		1 (310)	IBM TDB	1
	·			·

_	35	(((resist or photoresist) and (slop\$3 or	USPAT;	2003/07/22
		inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))	US-PGPUB; EPO; JPO;	15:19
		((grey or gray) same (mask or recicle))	IBM TDB	
_	0	((((resist or photoresist) and (slop\$3 or	DERWENT	2003/07/22
		inclin\$3 or taper\$3)) with (etch\$3)) and		15:32
		((grey or gray) same (mask or reticle)))		
		not us.pc.		0000/07/00
-	0		DERWENT	2003/07/22 15:32
		photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or		15:32
!		gray) same (mask or reticle)))) not		
		us.pc.		
_	2920	430/314,323-324.ccls. not ((((resist or	USPAT;	2003/01/17
ŀ		photoresist) and (slop\$3 or inclin\$3 or	US-PGPUB;	17:08
		taper\$3)) with (etch\$3)) and ((grey or	EPO; JPO;	
		gray) same (mask or reticle))) (("5962909") or ("5831266") or	IBM_TDB USPAT;	2003/01/17
-	6	("5962909") or ("5631266") or ("6201243")	US-PGPUB	09:20
		or ("20020043706")).PN.	05 10105	05.20
_	35	(((resist or photoresist) and (slop\$3 or	USPAT;	2003/01/17
		inclin\$3 or taper\$3)) with (etch\$3)) and	US-PGPUB;	15:37
		((grey or gray) same (photomask or mask	EPO; JPO;	
		or reticle))	IBM_TDB USPAT;	2003/01/17
-	. 29	<pre>(((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and</pre>	USPAT; US-PGPUB;	15:37
		((grey or gray) with (photomask or mask	EPO; JPO;	10.07
		or reticle))	IBM_TDB	
-	58	(((resist or photoresist) and (slop\$3 or	USPĀT;	2003/01/17
		inclin\$3 or taper\$3)) same (etch\$3)) and	US-PGPUB;	15:41
		((grey or gray) same (photomask or mask	EPO; JPO;	
	23	or reticle)) ((((resist or photoresist) and (slop\$3 or	IBM_TDB USPAT;	2003/07/22
-	23	inclin\$3 or taper\$3)) same (etch\$3)) and	US-PGPUB;	15:33
		((grey or gray) same (photomask or mask	EPO; JPO;	
		or reticle))) not ((((resist or	IBM_TDB	
		photoresist) and (slop\$3 or inclin\$3 or		
		taper\$3)) with (etch\$3)) and ((grey or		
		gray) same (photomask or mask or reticle)))		
_	2919	1	USPAT;	2003/07/22
	2313	photoresist) and (slop\$3 or inclin\$3 or	US-PGPUB;	15:35
		taper\$3)) with (etch\$3)) and ((grey or	EPO; JPO;	
		gray) same (photomask or mask or	IBM_TDB	
		reticle))) not (((((resist or		
		<pre>photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or</pre>		
		gray) same (photomask or mask or		
		reticle))) not ((((resist or photoresist)		
		and (slop\$3 or inclin\$3 or taper\$3)) with		
		(etch\$3)) and ((grey or gray) same		
l _	623	(photomask or mask or reticle)))) (mems or moems or microelectromechanical	USPAT;	2003/01/18
-	623	or micro adj electromechanical).ti.ab.	US-PGPUB;	11:46
		at mioro adj crootromcondiniodri, cr. ab.	EPO; JPO;	
			IBM_TDB	
-	26		USPAT;	2003/07/22
		or micro adj electromechanical).ti.ab.)	US-PGPUB;	15:36
		and (microbeam or microplatform or microsupport or (suspend\$3 with	EPO; JPO; IBM TDB	
		microsupport of (suspend33 with microstructure))	1211_121	
	884	(photolithograph\$6 or lithograph\$6 or	USPAT;	2003/01/18
		photoresist or resist) and etch\$3 and	US-PGPUB	13:38
	1	(204/192.14-192.15, 192.17, 192.23, 192.25		
	007	or 205/122-123,125).ccls.	HEDAT.	2003/01/19
-	827	((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and	USPAT; US-PGPUB	2003/01/18 13:39
		(204/192.14-192.15,192.17,192.23,192.25	JJ FGFUB	13.37
		or 205/122-123,125).ccls.) not		
		430/314,323-324.ccls.		

_	827	(((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25	USPAT; US-PGPUB; EPO; JPO;	2003/07/22 15:38
		or 205/122-123,125).ccls.) not 430/314,323-324.ccls.) not (((resist or	IBM_TDB	
		photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or		
<u>-</u>	17	<pre>gray) same (mask or reticle))) resistive adj evaporat\$3 and</pre>	USPAT;	2003/07/22
	1,	((photolithograph\$6 or photoresist or resist) same etch\$3)	US-PGPUB	15:39
-	6636	electroplat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)	USPAT; US-PGPUB	2003/01/20 15:35
-	34	adj layer) not ((((resist or photoresist)	USPAT; US-PGPUB;	2003/07/22 15:40
		and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same	EPO; JPO; IBM_TDB	
		<pre>(photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3</pre>	_	
		or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or		
		mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or		
		taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))))		
-	440	(resist or photoresist) and (air adj bridge)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/01/23 17:03
_	210	(resist or photoresist) same (air adj bridge)	USPAT; US-PGPUB; EPO; JPO;	2003/01/23 17:04
_	10		IBM_TDB USPAT;	2003/07/22
		bridge same (slop\$3 or inclin\$3 or taper\$3))	US-PGPUB; EPO; JPO; IBM TDB	15:41
-	1	((resist or photoresist) and ((microplatform or suspend\$3) same	USPAT; US-PGPUB;	2003/07/22
		(slop\$3 or inclin\$3 or taper\$3))) and ((grey or gray) with mask)	EPO; JPO; IBM TDB	20.11
_	2	(resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3))	USPAT; US-PGPUB;	2003/07/22 15:42
		Jame (313973 of filefilly) of capetys//	EPO; JPO; IBM TDB	
-	900	(resist or photoresist) and	USPAT; US-PGPUB;	2003/01/24 11:20
		((microplatform or suspend\$3) same (slop\$3 or inclin\$3 or taper\$3))	EPO; JPO; IBM TDB	11.20

- 16		USPAT;	2003/07/22
	(etch\$3)) and 430/320.ccls.) not	US-PGPUB;	15:42
	((((resist or photoresist) and (slop\$3 or	EPO; JPO;	
	inclin\$3 or taper\$3)) with (etch\$3)) and	IBM_TDB	
	((grey or gray) same (mask or reticle)))		
	not (((((resist or photoresist) and		
	(slop\$3 or inclin\$3 or taper\$3)) same		1
	(etch\$3)) and ((grey or gray) same		
	(photomask or mask or reticle))) not		
	((((resist or photoresist) and (slop\$3 or		
	inclin\$3 or taper\$3)) with (etch\$3)) and		
ļ. i	((grey or gray) same (photomask or mask		
	or reticle)))) not (430/314,323-324.ccls.		
	not ((((resist or photoresist) and		
1	(slop\$3 or inclin\$3 or taper\$3)) with		
	(etch\$3)) and ((grey or gray) same		
	(photomask or mask or reticle))) not		1
	(((((resist or photoresist) and (slop\$3		
	or inclin\$3 or taper\$3)) same (etch\$3))		
	and ((grey or gray) same (photomask or		,
	mask or reticle))) not ((((resist or		
	photoresist) and (slop\$3 or inclin\$3 or		,
	taper\$3)) with (etch\$3)) and ((grey or		1
	gray) same (photomask or mask or		
	reticle))))) not (((mems or moems or		
	microelectromechanical or micro adj	ŀ	
	electromechanical).ti.ab.) and (microbeam		
	or microplatform or microsupport or	1	
	(suspend\$3 with microstructure))) not		
	((((photolithograph\$6 or lithograph\$6 or		
	photoresist or resist) and etch\$3 and		
	(204/192.14-192.15,192.17,192.23,192.25		
	or 205/122-123,125).ccls.) not		
	430/314,323-324.ccls.) not (((resist or		
	photoresist) and (slop\$3 or inclin\$3 or		
	taper\$3)) with (etch\$3)) and ((grey or		
	gray) same (mask or reticle)))) not	ļ	
	(resistive adj evaporat\$3 and		
	((photolithograph\$6 or photoresist or		
	resist) same etch\$3)) not	:	
	(430/314,323-324.ccls. and (planarization		
	adj layer) not ((((resist or photoresist)		
	and (slop\$3 or inclin\$3 or taper\$3)) with		
	(etch\$3)) and ((grey or gray) same		
	(photomask or mask or reticle))) not		
	(((((resist or photoresist) and (slop\$3		
	or inclin\$3 or taper\$3)) same (etch\$3))		
	and ((grey or gray) same (photomask or		
	mask or reticle))) not (((resist or		
	photoresist) and (slop\$3 or inclin\$3 or		
	taper\$3)) with (etch\$3)) and ((grey or		
	gray) same (photomask or mask or		
	reticle))))) not ((resist or photoresist)		
	and (air adj bridge same (slop\$3 or		
	inclin\$3 or taper\$3))) not ((resist or		
	photoresist) and ((microbeam) same		
	(slop\$3 or inclin\$3 or taper\$3)))		
L	/stobas of incituas of caberasili	L	